

AMENDMENT TO CLAIMS

In the Claims:

Please **CANCEL** claims 21-35 without prejudice or disclaimer of the subject matter recited therein. Applicants expressly reserve the right to file one or more divisional or continuation applications directed to the subject matter recited in these claims.

A copy of all pending claims and a status of each are provided below.

Listing of Claims:

1. (Original) A method of evaluating the effect of defects on components in a semiconductor manufacturing process, said method comprising the steps of:
 - inspecting a component for defects using an inspection tool;
 - recording defect inspection data from the inspection tool;
 - accessing design data from a design data repository corresponding to the component being inspected;
 - modifying said design data for the component according to said defect inspection data;
 - and
 - analyzing said modified design data by applying a rule set to determine a final disposition of the component according to previously established criteria.
2. (Original) The method of claim 1, wherein the components being inspected comprise masks for semiconductor wafers and the components are combined to generate a mask layer.

3. (Original) The method of claim 1, wherein the inspection tool is an optical inspection device and said defect inspection data include defect location, defect size and a designation of defect type as clear or opaque.

4. (Original) The method of claim 2, wherein said final disposition of the mask being inspected includes one of: scrapping the mask, repairing the mask, and accepting the mask.

5. (Original) The method of claim 2, wherein said previously established criteria include a determination as to whether a defect would be likely to cause product failure.

6. (Original) The method of claim 3, wherein said designation of defect type as clear or opaque is performed by one of manually by an operator and a defect classification tool.

7. (Original) The method of claim 3, wherein said defect inspection data comprise intensity contour plots, and the method for modifying said design data includes the following steps:

creating a simulated wafer image of the defect; and
merging said simulated wafer image into a simulated wafer image of a semiconductor chip.

8. (Original) The method of claim 1, wherein said design data repository comprises a database suitable for storage of large data files, and wherein said database includes design data for each component being inspected.

9. (Original) The method of claim 2, wherein the method for modifying said design data comprises the step of generating a representative defect shape for each mask layer being inspected corresponding to defects from said defect inspection data.

10. (Original) The method of claim 2, wherein said rule set includes criteria for analyzing both intra-level and inter-level problems of the mask layer corresponding to said inspection defect data.

11. (Original) A method of evaluating the effect of defects on masks for semiconductor wafers, said method comprising the steps of:

inspecting a mask for defects using an inspection tool; recording defect inspection data from the inspection tool;

accessing design data from a design data repository corresponding to a level of a mask layer being inspected;

modifying said design data for said level of a mask layer according to said defect inspection data; and

analyzing said modified design data by applying a rule set to determine a final disposition of the mask according to previously established criteria.

12. (Original) The method of claim 11, wherein said final disposition of the mask includes one of: scrapping the mask, repairing the mask, and accepting the mask, and said previously established criteria includes a determination as to whether a defect would be likely to cause product failure.

13. (Original) The method of claim 12, said method further comprising the steps of:
repairing masks in which defects identified from the inspection tool are within acceptable limits; and
scrapping masks in which defects identified from the inspection tool are outside acceptable limits.

14. (Original) The method of claim 11, further comprising the step of determining if a defect identified from the inspection tool will be resolved on a wafer by the photolithographic process.

15. (Original) The method of claim 14, wherein said method for determining if said defect will be resolved on the wafer is one of a set of heuristic rules and a commercially available tool or software program.

16. (Original) A system for evaluating the effect of defects in masks for semiconductor wafers during pre-shipment inspection and pre-acceptance inspection of masks for semiconductor wafers, said system comprising:

an inspection tool for inspecting a mask for defects; a recording medium for storing said defect inspection data from the inspection tool;

a design data repository containing design level data for a level of a mask layer being inspected;

a computer program for modifying said design data for said level of mask layer according to said defect inspection data; and

a rule set for analyzing said modified design data to determine a final disposition of the mask according to previously established criteria.

17. (Original) The system of claim 16, wherein said final disposition of the mask includes one of: scrapping the mask, repairing the mask, and accepting the mask, and said previously established criteria includes a determination as to whether a defect would be likely to cause product failure.

18. (Original) The system according to claim 17, wherein the inspection tool is an optical inspection device and defect inspection data include defect location, defect size and a designation of defect type as clear or opaque.

19. (Original) A computer readable medium comprising code for causing a computer to implement steps of a method for evaluating the effect of defects on masks in a semiconductor manufacturing process, said method comprising:

inspecting a mask for defects using an inspection tool; recording defect inspection data from the inspection tool;

accessing design data from a design data repository corresponding to a level of a mask layer being inspected;

modifying said design data for said level of a mask layer according to said defect inspection data; and

analyzing said modified design data by applying a rule set data to determine a final disposition of the mask according to previously established criteria.

20. (Original) The method of claim 19, wherein said final disposition of the mask includes one of: scrapping the mask, repairing the mask, and accepting the mask, and said previously established criteria includes a determination as to whether a defect would be likely to cause product failure.

Claims 21-35 (Canceled).